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⑤④ X-ray exposure apparatus.

⑤⑦ An X-ray apparatus is disclosed which includes a mirror (2) having a reflection surface, for expanding an X-ray beam (1) in a predetermined direction, a detecting device (8a, 8b) for detecting a relative positional relationship between the X-ray beam and the reflection surface with respect to a direction perpendicular to the reflection surface, and an adjusting device (6) for adjusting the relative position of the X-ray beam and the reflection surface on the basis of the detection. Also disclosed is an exposure apparatus and a semiconductor device manufacturing method using the X-ray apparatus.

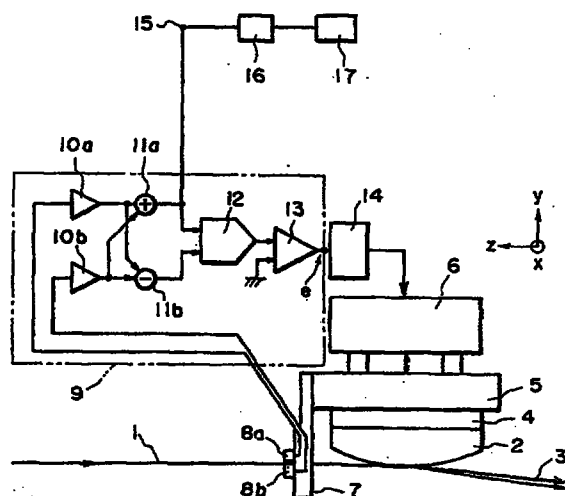


FIG. 37

This Sheet Has Been Replaced



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